

IN THE CLAIMS:

Please amend claims 1-9 as shown below, in which deleted terms are shown with strikethrough and/or added terms are shown with underscoring. Also, please add new claims 10-20 as shown below.

1. (Currently amended) A paddle type developing apparatus of photoresist in which a developing solution from a nozzle is supplied to an object to be treated, which is held by a chuck device including a spinner, and the developing solution on the object to be treated is thrown off by rotating a the spinner ~~constituting the chuck device~~ after a lapse of a prescribed time, wherein the paddle type developing apparatus comprises a nozzle which mixes a developing solution and air and spouts a developing solution in mist form and at least part of a developing solution pipe leading to this nozzle is disposed within a circulation path of temperature regulating water.
2. (Currently amended) The developing apparatus according to claim 1, wherein part of the circulation path of said temperature regulating water is formed in said chuck device and the temperature of said chuck device is adjusted in said part of ~~this~~ the circulation path.
3. (Currently amended) The developing apparatus according to claim 1, wherein at least part of an air pipe which supplies air to be mixed with said developing solution is disposed within the circulation path of said temperature regulating water.
4. (Currently amended) The developing apparatus according to claim 1, wherein ~~this~~ the developing apparatus further comprises a blower which feeds ~~the~~ temperature-regulated air into the developing apparatus and a preheating device which ~~beforehand~~ heats the object to be treated before ~~the~~ transfer of ~~this~~ the object into the developing apparatus.
5. (Currently amended) The developing apparatus according to claim 1, wherein the chuck device includes a cup and a ~~bottom~~ surface of a said cup is provided with a projecting body which prevents the developing solution from flowing behind a rear surface of the ~~wafer~~ object to be treated.

6. (Currently amended) The developing apparatus according to claim 1, wherein the spinner is provided with convex projections which generate air currents in a radial direction on a rear surface of the ~~substrate, which is the object to be treated, by cutting air by rotation~~ when the spinner is rotated.

7. (Currently amended) The developing apparatus according to claim 1, ~~wherein~~ further comprising an antiscattering cup in which said nozzle which spouts a developing solution in mist form is disposed ~~within an antiscattering cone~~.

8. (Currently amended) A developing method which uses the developing apparatus according to ~~any one of claims 1 to 7~~ claim 1, wherein a regulated temperature of said developing solution, a regulated temperature of said chuck device, a regulated temperature of said air to be mixed with the developing solution and/or a regulated temperature of ~~said~~ air to be fed into the developing apparatus is not less than 30°C but less than 60°C.

9. (Currently amended) A developing method which uses the developing apparatus according to ~~any one of claims 1 to 7~~ claim 1, wherein ~~this~~ the developing method is applied to the development treatment of a thick film photoresist of not less than 10 μm.

10. (New) A developing method according to claim 8, wherein the developing method is applied to the development treatment of a thick film photoresist of not less than 10 μm.

11. (New) A developing method according to claim 8, wherein each of the regulated temperature of said developing solution, the regulated temperature of said chuck device, the regulated temperature of said air to be mixed with the developing solution and the regulated temperature of said air to be fed into the developing apparatus is not less than 30°C but less than 60°C.

12. (New) The developing apparatus according to claim 5, wherein said cup is disposed with a bottom surface thereof facing the object to be treated in close proximity thereto, and said projecting body is disposed on said bottom surface near an outer periphery of the object to be treated.

13. (New) The developing apparatus according to claim 6, wherein projecting edges of said convex projections are rounded.

14. (New) The developing apparatus according to claim 7, wherein said antiscattering cup is cone shaped.

15. (New) A developing method which uses the developing apparatus according to claim 4, wherein a regulated temperature of said developing solution, a regulated temperature of said chuck device, a regulated temperature of said air to be mixed with the developing solution and/or a regulated temperature of air to be fed into the developing apparatus is not less than 30°C but less than 60°C.

16. (New) A developing method which uses the developing apparatus according to claim 4, wherein the developing method is applied to the development treatment of a thick film photoresist of not less than 10 μm .

17. (New) A developing method which uses the developing apparatus according to claim 5, wherein a regulated temperature of said developing solution, a regulated temperature of said chuck device, a regulated temperature of said air to be mixed with the developing solution and/or a regulated temperature of air to be fed into the developing apparatus is not less than 30°C but less than 60°C.

18. (New) A developing method which uses the developing apparatus according to claim 5, wherein the developing method is applied to the development treatment of a thick film photoresist of not less than 10 μm .

19. (New) A paddle type developing apparatus of photoresist in which a developing solution from a nozzle is supplied to an object to be treated, which is held by a chuck device including a spinner, and the developing solution on the object to be treated is thrown off by rotating the spinner after a lapse of a prescribed time, wherein the paddle type developing apparatus comprises a nozzle which mixes a developing solution and air and spouts a developing solution in mist form and a temperature regulating mechanism which regulates temperature of at least part of a developing solution pipe leading to the nozzle.

20. (New) The developing apparatus according to claim 19, wherein said temperature regulating mechanism also regulates temperatures of said chuck device and at least part of an air pipe which supplies air to be mixed with said developing solution by said nozzle.